

SEVENTH SUPPLEMENTAL FORM PTO-1449	SERIAL NO. 10/634,250	CASE NO. 10022/350
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANTS' INFORMATION DISCLOSURE STATEMENT	FILING DATE August 5, 2003	GROUP ART UNIT 2161
Confirmation No. 7779	APPLICANTS: DeSchryver et al.	

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER Number-Kind Code (if known)	DATE	NAME	CLASS/ SUBCLAS S	FILING DATE
	H1	6,886,007 B2	04/26/2005	Leymann et al.		
	H2	2002/0026297 A1	02/28/2002	Leymann et al.		

EXAMINER INITIAL	OTHER ART – NON PATENT LITERATURE DOCUMENT (Include name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date page(s), volume-issue number(s), publisher, city and/or country where published.	
	H3	United States Patent and Trademark Office Decision on Appeal dated March 15, 2011 for corresponding U.S. Patent Application Serial No. 10/367,618.
	H4	Examiner's Second Report dated November 2, 2010 for corresponding Australian Patent Application No. 2004263985.
	H5	Examiner's First Report dated October 7, 2010 for corresponding Canadian Patent Application No. 2,534,666.
	H6	Vitharana et al., "Knowledge-Based Repository Scheme for Storing and Retrieving Business Components: A Theoretical Design and an Empirical Analysis," IEEE Transactions on Software Engineering, vol. 29, no. 7, July 2003, pp. 649-664, ISSN: 0098-5589.
	H7	Delen et al., "An Integrated Toolkit for Enterprise Modeling and Analysis," December 5, 1999, Winter Simulation Conference Proceedings, 1999, Phoenix, Arizona, USA, Piscataway, NJ, IEEE, pp. 289-297, ISBN: 0-7803-5780-9.
	H8	Breunese et al., "Libraries of Reusable Models: Theory and Application," Simulation, vol. 71, no. 1, 1998, ISSN: 0037-5497.

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.